

9601054-1 4
1705

- 1 -

This Sheet Has Been Replaced


PHOTOINITIATOR COMPOSITIONS AND
PHOTOSENSITIVE MATERIALS USING THE SAME

BACKGROUND OF THE INVENTION

This invention relates to an N-aryl- α -amino acid, a photoinitiator composition using an N-aryl- α -amino acid and a 3-substituted coumarin and/or an
5 azabenzalcylohexanone, a photoinitiator composition using an N-aryl- α -amino acid, a 3-substituted coumarin and a titanocene, a photoinitiator composition using a 3-substituted coumarine, a titanocene and an oxime ester, a photosensitive composition using one member selected
10 from the group consisting of these photoinitiator compositions, a photosensitive material using one member selected from the group consisting of these photoinitiator compositions and a process for forming patterns using the photosensitive material.

15 Photosensitive compositions are widely used for forming letterpresses, relief images, photoresists, and the like generally using ultraviolet (UV) light as a light source, and are desired to have a higher sensitivity. Particularly, when photosensitive compositions
20 are used for scanning light exposure by means of laser beams, they are required not only to be highly sensitive but also to have sufficiently high sensitivity to visible light (458, 488, 514.5 nm) which is an output wavelength of an argon laser. Further, in the case of photo-
25 sensitive polyimide for thick films usable in semi-

THIS SHEET HAS BEEN
REPLACED



- 2 -

conductors, it is required to have sufficient sensitivity to a g-line stepper using monochromic light (light of 435 nm), a contact exposing equipment using the whole wavelengths of a mercury lamp, and a mirror projection
5 type exposing equipment, and to have good photosensitive wavelength properties.

In order to enhance the sensitivity, various studies have been done on photoinitiators. As the photoinitiators, there have been known benzoin and
10 derivatives thereof, substituted or non-substituted polynuclear quinones, etc. But substances having excellent sensitivity meeting the above-mentioned objects have not been known yet.

On the other hand, polyimides or precursors
15 thereof having photo-patterning properties by themselves are called as "photosensitive polyimides", which are used as a surface protective film for semiconductors. In order to impart photosensitivity to polyimides, various methods have been known. For example, Japanese Patent
20 Examined Publication (JP-B) No. 55-41422 proposes a method for esterifying a poly(amic acid) with hydroxy acrylate. Japanese Patent Unexamined Publication (JP-A) Nos. 57-170929 and 54-145794 propose to introduce a photosensitive group by means of a salt bond by mixing
25 poly(amic acid) with amino acrylate. In the case of the former (JP-B), the photo-patterning properties are relatively good, but since it is difficult to obtain a high polymer, removal of photosensitive groups becomes

THIS SHEET HAS BEEN
REPLACED



easily incomplete, resulting in showing a defect of poor film properties. On the other hand, in the latter case (two JP-A's), it is easy to obtain a high polymer and good film properties due to easy volatility, but photo-
5 patterning properties are not sufficient. Particularly, in the case of photosensitive polyimides for thick films having a film thickness of 5 μm or more after cured, there is a problem in that no good patterning properties is obtained when exposed to light using an i-line stepper
10 (light of 365 nm), a g-line stepper (light of 435 nm), a mirror projection type exposing equipment using whole wavelengths of a mercury lamp.

SUMMARY OF THE INVENTION

It is an object of the present invention to
15 provide a photoinitiator composition used for a photosensitive composition and a photosensitive material which have an excellent photosensitive property, the photosensitive composition, the photosensitive material, a process for forming patterns using the photosensitive
20 material, namely, to provide an N-aryl- α -amino acid effective as a photoinitiator, a photoinitiator composition using an N-aryl- α -amino acid and a 3-substituted coumarin and/or an azabenzalcylohexanone, a photoinitiator composition using an N-aryl- α -amino
25 acid, a 3-substituted coumarin and a titanocene, a photoinitiator composition using a 3-substituted coumarine, a titanocene and an oxime ester, a

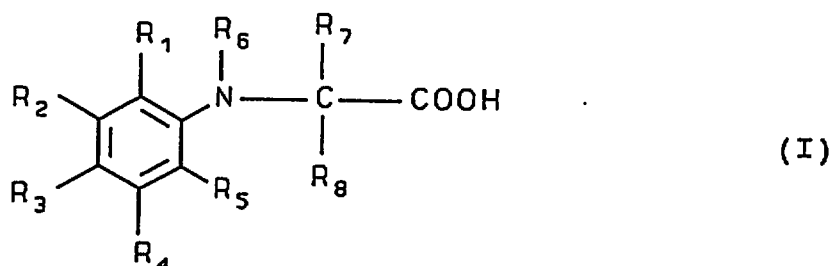


- 4 -

photosensitive composition using one member selected from the group consisting of these photoinitiator compositions, a photosensitive material using one member selected from the group consisting of these photoinitiator compositions, and a
 5 process for forming patterns using such photosensitive material overcoming the above-mentioned problems of prior art.

According to the new compositions of the present invention, the above problem that no good patterning
 10 properties is obtained when exposed to light using an i-line stepper, a g-line stepper, a mirror projection type exposing equipment using whole wave-lengths of a mercury lamp can be solved.

The present invention provides an N-aryl- α -amino
 15 acid of the formula:



wherein R_1 , R_2 , R_3 , R_4 and R_5 are independently a hydrogen atom, a halogen atom, an alkyl group having 1 to 4 carbon atoms, a cyano group, an alkoxycarbonyl group having 2 to 10 carbon atoms, a carboxyamido group, or an alkylsulfonyl group having
 20 1 to 4 carbon atoms and said alkyl moiety able to be

THIS SHEET HAS BEEN REPLACED

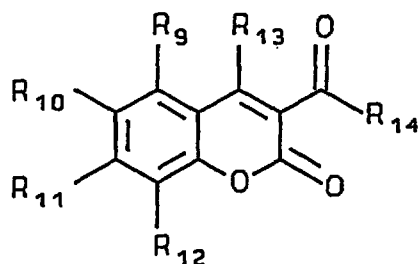


substituted with a cyano group, and at least one of R_1 through R_5 is a cyano group or an alkylsulfonyl group having 1 to 4 carbon atoms; R_6 is a hydrogen atom, an alkyl group having 1 to 12 carbon atoms, a cycloalkyl group, a hydroxyalkyl group having 1 to 12 carbon atoms, an alkoxyalkyl group having 2 to 12 carbon atoms, an aminoalkyl group having 1 to 12 carbon atoms, or an aryl group; and R_7 and R_8 are independently a hydrogen atom or an alkyl group having 1 to 8 carbon atoms.

The present invention also provide a photoinitiator composition (A) comprising

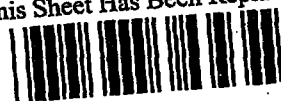
an N-aryl- α -amino acid of the formula (I'), and

at least one member selected from the group consisting of a 3-substituted coumarin compound of the formula:

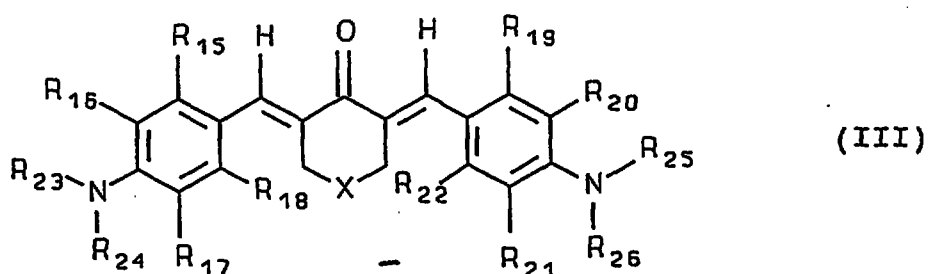


(II)

wherein R_9 , R_{10} , R_{11} , R_{12} and R_{13} are independently a hydrogen atom, an amino group substituted with an alkyl group having 1 to 5 carbon atoms, an amino group substituted with two alkyl groups having 1 to 5 carbon atoms, an alkoxy group having 1 to 5 carbon atoms, an acyloxy group, an aryl group, a halogen atom, or a thioalkyl group having 1 to 5 carbon atoms; and R_{14} is a



non-substituted phenyl group, a biphenyl group, a naphthyl group, a thienyl group, a benzofuryl group, a furyl group, a pyridyl group, a coumarinyl group, an amino group, an amino group substituted with one or more alkyl groups having 1 to 5 carbon atoms, a cyano group, an alkoxy group having 1 to 5 carbon atoms, an alkyl group having 1 to 5 carbon atoms, a halogen atom, a haloalkyl group, a formyl group, an alkoxycarbonyl group having 1 to 5 carbon atoms, an acyloxy group having 1 to 5 carbon atoms, a phenyl group substituted with an acyloxy group having 1 to 5 carbon atoms, a cyano group, an alkoxy group or an acyl group having 1 to 5 carbon atoms, said biphenyl group, said naphthyl group, said thienyl group, said benzofuryl group, 10 said furyl group, said pyridyl group or coumarinyl group being able to be substituted by an acyloxy group having 1 to 5 carbon atoms or an acyl group having 1 to 5 carbon atoms, and an azabenzalcylohexanone compound of the formula:

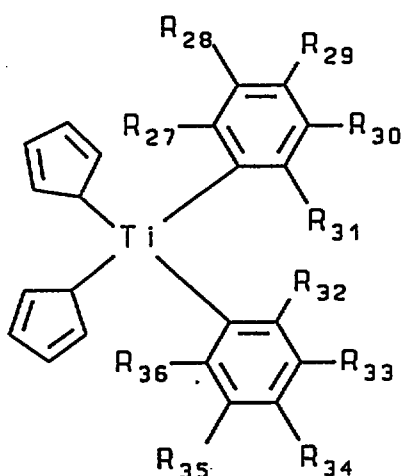


wherein R_{15} , R_{16} , R_{17} , R_{18} , R_{19} , R_{20} , R_{21} and R_{22} are independently a 15 hydrogen atom, a chlorine atom, a bromine atom, an alkyl group having 1 to 12 carbon atoms, an aryl group or an alkoxy



group having 1 to 12 carbon atoms; and R_{23} , R_{24} , R_{25} and R_{26} are independently an alkyl group having 1 to 6 carbon atoms; X is an imino group which may be substituted with an alkyl group having 1 to 12 carbon atoms, an aralkyl group having 7 to 20 carbon atoms, an aryl group, an acyl group having 2 to 12 carbon atoms, an arylcarbonyl group having 7 to 20 carbon atoms, an alkoxycarbonyl group having 2 to 12 carbon atoms, or an aryloxycarbonyl group having 7 to 20 carbon atoms.

The present invention further provides a
 10 photoinitiator composition (B) comprising
 an N-aryl- α -amino acid of the formula (I'),
 a 3-substituted coumarin compound of the formula
 (II), and
 a titanocene compound of the formula:



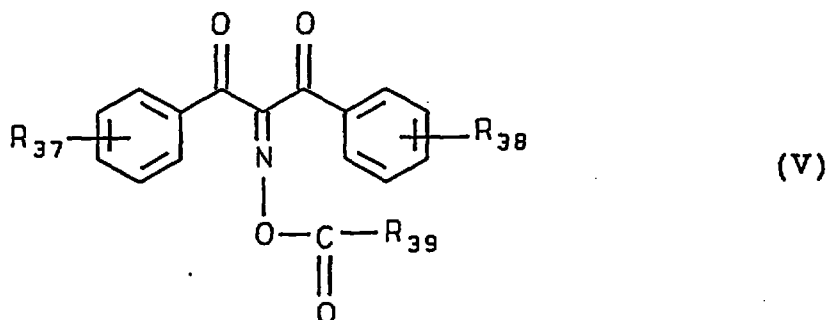
(IV)

15 wherein R^{27} through R^{36} are independently a hydrogen atom, a halogen atom, an alkoxy group having 1 to 20 carbon atoms or a heterocyclic ring such as 1-pyrrolyl, 2-pyrrolyl, 3-pyrrolyl, imidazolyl, pyrazolyl, etc, said heterocyclic ring



being bound to a benzene ring via an alkylene group or substituted with one or more alkyl groups, amino groups and alkoxy groups.

The present invention still further provides a
 5 photoinitiator composition (C) comprising
 a 3-substituted coumarin compound of the formula
 (II),
 a titanocene compound of the formula (IV), and
 an oxime ester compound of the formula:

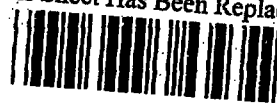


wherein R_{37} and R_{38} are independently a hydrogen atom, an alkyl group having 1 to 6 carbon atoms, an alkoxy group having 1 to 6 carbon atoms or a nitro group; and R_{39} is an alkyl group having 1 to 12 carbon atoms, an alkoxy group having 1 to 12 carbon atoms, a phenyl group, a benzyl group, $-OCH_2CH_2OCH_3$ or $-CO_2CH_2CH_3$.

The present invention also provide a
 photosensitive composition comprising

an addition polymerizable compound having a
 boiling point of 100°C or higher under 1 atmosphere, and
 a photoinitiator composition (A), (B) or (C).

This Sheet Has Been Replaced



- 9 -

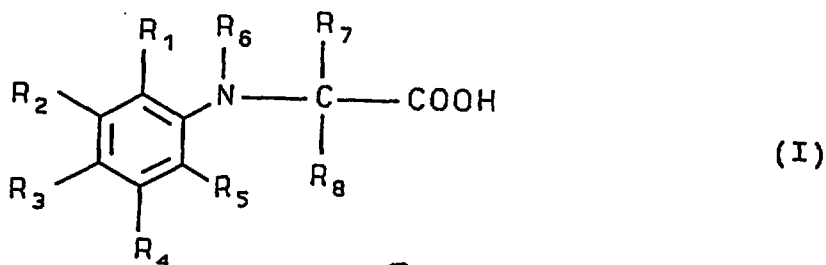
The present invention further provides a photo-sensitive material comprising

- (a) a poly(amic acid),
- (b) a compound having one or more carbon-carbon double bonds dimerizable or polymerizable by actinic radiation and one or more amino groups or a quaternary salt thereof, and
- (c) a photoinitiator composition (A), (B) or (C).

The present invention still further provides a process for forming a pattern using the photosensitive material mentioned above.

DESCRIPTION OF THE PREFERRED EMBODIMENTS

The N-aryl- α -amino acid of the present invention 5 is represented by the formula:



wherein R_1 , R_2 , R_3 , R_4 and R_5 are independently a hydrogen atom, a halogen atom, an alkyl group having 1 to 4 carbon atoms, a cyano group, an alkyloxycarbonyl group having 2 to 10 carbon

THIS SHEET HAS BEEN
REPLACED



atoms, a carboxyamido group, or an alkylsulfonyl group having 1 to 4 carbon atoms and said alkyl moiety able to be substituted with a cyano group, and at least one of R_1 through R_3 is a cyano group or an alkylsulfonyl group having 1 to 4 carbon atoms; R_4 is a hydrogen atom, an alkyl group having 1 to 12 carbon atoms, a cycloalkyl group preferably having 3 to 7 carbon atoms, a hydroxyalkyl group having 1 to 12 carbon atoms, an alkoxyalkyl group having 2 to 12 carbon atoms, or a substituted or non-substituted aryl group preferably having 6 to 10 carbon atoms such as phenyl, naphthyl, etc; and R_7 and R_8 are independently a hydrogen atom or an alkyl group having 1 to 8 carbon atoms.

When the compound of the formula (I) is used in a photoinitiator composition, the limitation of "and at least one of R_1 through R_3 is a cyano group or an alkylsulfonyl group having 1 to 4 carbon atoms" is not necessary [herein such a compound is referred to as "N-aryl- α -amino acid of the formula (I')"].

The N-aryl- α -amino acid of the formula (I) or (I') can be produced, for example, by aromatic nucleophilic substitution of a corresponding substituted halobenzene with a glycine compound using an analogous process.

More concretely, the aromatic nucleophilic substitution can be carried out generally by reacting a substituted halobenzene and a glycine compound in about equimolar amounts in a polar aprotic solvent such as acetone, dimethylsulfoxide, N-methyl-pyrrolidone, N,N-dimethylacetamide, N,N-dimethylformamide, tetrahydrofuran, sulfolane, methyl ethyl ketone, ethylene



carbonate, etc., in the presence of a basic compound at room temperature to about 100°C. As the basic compound, there can be used sodium carbonate, potassium carbonate, etc.

Examples of the compound of the formula (I) or (I') are as follows:

N-(p-methylsulfonylphenyl)-N-methylglycine
(Compound No. 1),
N-(p-methylsulfonylphenyl)-N-ethylglycine,
N-(p-methylsulfonylphenyl)-N-n-propylglycine,
N-(p-methylsulfonylphenyl)-N-n-butylglycine,
N-(p-cyanophenyl)-glycine (Compound No. 2),
N-(p-cyanomethylsulfonylphenyl)-N-methyl-
glycine,
N-(p-cyanomethylsulfonylphenyl)-N-ethylglycine,
N-(p-cyanomethylsulfonylphenyl)-N-n-propyl-
glycine,
N-(p-cyanomethylsulfonylphenyl)-N-n-butyl-
glycine,
N-(p-ethylsulfonylphenyl)-N-methylglycine,
N-(p-ethylsulfonylphenyl)-N-ethylglycine,
N-(p-ethylsulfonylphenyl)-N-n-propylglycine,
N-(p-ethylsulfonylphenyl)-N-n-butylglycine,
N-(p-2'-cyanoethylsulfonylphenyl)-N-methyl-
glycine,
N-(p-2'-cyanoethylsulfonylphenyl)-N-ethyl-
glycine,



N-(p-2'-cyanoethylsulfonylphenyl)-N-n-propyl-
glycine,

N-(p-2'-cyanoethylsulfonylphenyl)-N-n-butyl-
glycine,

N-(p-cyanophenyl)-N-methylglycine (Compound No.
3),

N-(p-cyanophenyl)-N-ethylglycine,

N-(p-cyanophenyl)-N-n-propylglycine,

N-(p-cyanophenyl)-N-n-butylglycine,

N-(p-n-propylsulfonylphenyl)-N-methylglycine,

N-(p-n-butylsulfonylphenyl)-N-methylglycine,

N-(p-carboxyamidophenyl)-N-methylglycine,

N-(p-carboxyamidophenyl)-N-ethylglycine,

N-(p-carboxyamidophenyl)-N-n-propylglycine,

N-(p-carboxyamidophenyl)-N-n-butylglycine,

N-(p-ethoxycarbonylphenyl)-N-methylglycine,

N-(p-ethoxycarbonylphenyl)-N-ethylglycine,

N-(p-ethoxycarbonylphenyl)-N-n-propylglycine,

N-(p-ethoxycarbonylphenyl)-N-n-butylglycine,

N-(p-methoxycarbonylphenyl)-N-methylglycine,

N-(p-methoxycarbonylphenyl)-N-ethylglycine,

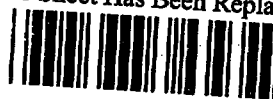
N-(p-methoxycarbonylphenyl)-N-n-propylglycine,

N-(p-methoxycarbonylphenyl)-N-n-butylglycine,

etc.

These compounds can be used singly or as a
mixture thereof, when used as a photoinitiator.

These compounds are effective as a photo-

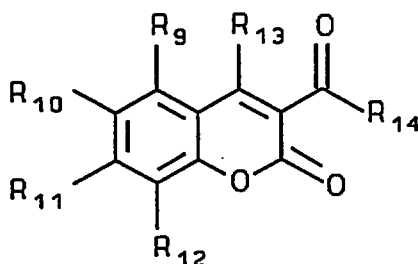


initiator which generates active radicals by the action of UV and visible light in combination of one or more suitable photosensitizers.

A photoinitiator composition (A) of the present invention comprises:

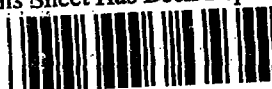
an N-aryl- α -amino acid of the formula (I') mentioned above, and

at least one member selected from the group consisting of a 3-substituted coumarin compound of the formula:

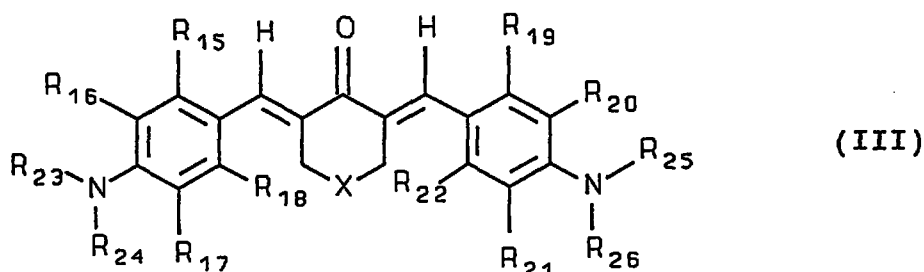


(II)

wherein R_9 , R_{10} , R_{11} , R_{12} and R_{13} are independently a hydrogen atom, an amino group substituted with an alkyl group having 1 to 5 carbon atoms, an amino group substituted with two alkyl groups having 1 to 5 carbon atoms, an alkoxy group having 1 to 5 carbon atoms, an acyloxy group, an aryl group such as phenyl, naphthyl, etc., a halogen atom, or a thioalkyl group having 1 to 5 carbon atoms; and R_{14} is a non-substituted phenyl group, a biphenyl group, a naphthyl group, a thienyl group, a benzofuryl group, a furyl group, a pyridyl group, a coumarinyl group, an amino group, an amino group substituted with one or more alkyl groups having 1 to 5 carbon atoms, a cyano group, an alkoxy



group having 1 to 5 carbon atoms, an alkyl group having 1 to 5 carbon atoms, a halogen atom, a haloalkyl group, a formyl group, an alkoxycarbonyl group having 1 to 5 carbon atoms, an acyloxy group having 1 to 5 carbon atoms, a phenyl group substituted with an acyloxy group having 1 to 5 carbon atoms, a cyano group, an alkoxy group, or an acyl group having 1 to 5 carbon atoms, said biphenyl group, said naphthyl group, said thienyl group, said benzofuryl group, said furyl group, said pyridyl group or said coumarinyl group being able to be substituted with an acyloxy group having 1 to 5 carbon atoms or an acyl group having 1 to 5 carbon atoms, and an azabenzalicyclohexanone compound of the formula:



wherein R_{15} , R_{16} , R_{17} , R_{18} , R_{19} , R_{20} , R_{21} and R_{22} are independently a hydrogen atom, a chlorine atom, a bromine atom, an alkyl group having 1 to 12 carbon atoms, an aryl group such as phenyl, naphthyl, etc. or an alkoxy group having 1 to 12 carbon atoms; and R_{23} , R_{24} , R_{25} and R_{26} are independently an alkyl group having 1 to 6 carbon atoms; X is an imino group which may be substituted with an alkyl group having 1 to 12 carbon atoms, an aralkyl group having 7 to 20 carbon atoms such as benzyl, phenethyl, etc., an aryl group such as



- 15 -

phenyl, naphthyl, etc., an acyl group having 2 to 12 carbon atoms, an arylcarbonyl group having 7 to 20 carbon atoms, an alkoxycarbonyl group having 2 to 12 carbon atoms, or an aryloxycarbonyl group having 7 to 20 carbon atoms.

5 Examples of the 3-substituted coumarin compound of the formula (II) are as follows:

3-benzoylcoumarin,
3-benzoyl-7-methoxycoumarin,
3-benzoyl-5,7-dimethoxycoumarin,
10 3-(4'-cyanobenzoyl)-coumarin,
3-(4'-cyanobenzoyl)-7-methoxycoumarin,
3-(4'-cyanobenzoyl)-5,7-dimethoxycoumarin,
3-thienylcarbonylcoumarin,
7-methoxy-3-thienylcarbonyl-coumarin,
15 5,7-dimethoxy-3-thienylcarbonyl-coumarin,
7-diethylamino-3-thienylcarbonyl-coumarin,
7-dimethylamino-3-thienylcarbonyl-coumarin,
3-(4'-methoxybenzoyl) coumarin,
3-(4'-methoxybenzoyl)-7-methoxycoumarin,
20 3-(4'-methoxybenzoyl)-5,7-dimethoxycoumarin,
3,3'-carbonylbis-(7-diethylaminocoumarin),
3,3'-carbonylbis-(7-methoxycoumarin),
3,3'-carbonylbis-(5,7-dimethoxycoumarin), etc.

These compounds can be used singly or as a mixture thereof.

Examples of the azabenzalcylohexanone compound of the formula (III) are as follows:

THIS SHEET HAS BEEN
REPLACED



- 16 -

2,6-bis(p-N,N-diethylaminobenzal)-4-methyl-4-azacyclohexanone,

2,6-bis(p-N,N-dimethylaminobenzal)-4-methyl-4-azacyclohexanone,

2,6-bis(p-N,N-diethylaminobenzal)-4-ethyl-4-azacyclohexanone,

2,6-bis(p-N,N-dimethylaminobenzal)-4-ethyl-4-azacyclohexanone,

2,6-bis(p-N,N-diethylaminobenzal)-4-n-propyl-4-azacyclohexanone,

2,6-bis(p-N,N-dimethylaminobenzal)-4-n-propyl-4-azacyclohexanone,

2,6-bis(p-N,N-diethylaminobenzal)-4-phenethyl-4-azacyclohexanone,

2,6-bis(p-N,N-dimethylaminobenzal)-4-benzyl-4-azacyclohexanone,

2,6-bis(p-N,N-dimethylaminobenzal)-4-acetyl-4-azacyclohexanone,

2,6-bis(p-N,N-dimethylaminobenzal)-4-benzoyl-4-azacyclohexanone, etc.

These compounds can be synthesized by the method shown in U.S. Patent No. 4,987,057.

These compounds can be used singly or as a mixture thereof.

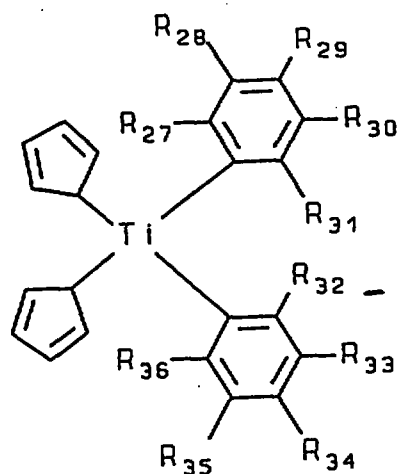
The N-aryl- α -amino acid of the formula (I') and the 3-substituted coumarin compound of the formula (II) and/or the azabenzalcylohexanone compound of the formula (III) may be used in various proportions, but the N-aryl-



α -amino acid by the formula (I') is preferably used in a larger amount than that of the compound of the formula (II) and/or (III). Generally, in case of using either the compound of the formula (II) or (III), the compound of the formula (II) or (III) is used in an amount of 1 to 100 parts by weight per 100 parts by weight of the compound of the formula (I'), and in case of using both the compounds of the formulae (II) and (III), a total amount of the compounds of the formulae (II) and (III) is used in an amount of 1 to 100 parts by weight per 100 parts by weight of the compound of the formula (I').

Another photoinitiator composition (B) of the present invention comprises

- an N-aryl- α -amino acid of the formula (I'),
- a 3-substituted coumarin compound of the formula (II), and
- a titanocene compound of the formula:



(IV)



wherein R_{27} through R_{36} are independently a hydrogen atom, a halogen atom, an alkoxy group having 1 to 20 carbon atoms or a heterocyclic ring such as pyrrole, etc., said heterocyclic ring being bound to a benzene ring via an alkylene group or substituted with one or more alkyl groups, amino groups and alkoxy groups.

Examples of the titanocene compound of the formula (IV) are as follows:

bis(cyclopentadienyl)-bis[2,6-difluoro-3-{2-(1H-pyrrol-1-yl)ethyl}phenyl] titanium,

bis(cyclopentadienyl)-bis[2,6-difluoro-3-{2-(1H-pyrrol-1-yl)propyl}phenyl] titanium,

bis(cyclopentadienyl)-bis[2,6-difluoro-3-{2-(1H-pyrrol-1-yl)methyl}phenyl] titanium,

bis(cyclopentadienyl)-bis[2,6-difluoro-3-(pyrrol-1-yl)phenyl] titanium,

bis(cyclopentadienyl)-bis[2,6-difluoro-3-(2,5-dimethylpyrrol-1-yl)phenyl] titanium,

bis(cyclopentadienyl)-bis[2,6-difluoro-3-(2,5-diethylpyrrol-1-yl)phenyl] titanium,

bis(cyclopentadienyl)-bis[2,6-difluoro-3-(2,5-diisopropylpyrrol-1-yl)phenyl] titanium,

bis(cyclopentadienyl)-bis[2,6-difluoro-3-(2,5-bisdimethylaminopyrrol-1-yl)phenyl] titanium,

bis(cyclopentadienyl)-bis[2,6-difluoro-3-(2,5-dimethyl-3-methoxypyrrol-1-yl)phenyl] titanium,

bis(cyclopentadienyl)-bis[2,6-difluoro-3-methoxyphenyl] titanium,



bis(cyclopentadienyl)-bis[2,6-difluoro-3-ethoxyphenyl] titanium,

bis(cyclopentadienyl)-bis[2,6-difluoro-3-isopropoxyphenyl] titanium,

bis(cyclopentadienyl)-bis[2,6-difluoro-3-n-propoxyphenyl] titanium, etc.

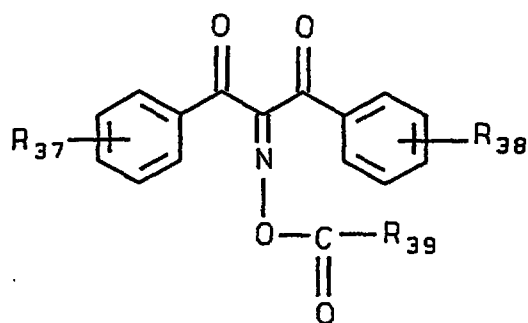
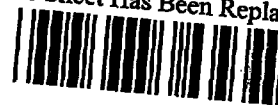
These titanocene compounds can be used singly or as a mixture thereof.

The compound of the formula (II) and the compound of the formula (IV) may be used in various proportions, but the compound of the formula (II) is preferably used in an amount of 1 to 100 parts by weight, and the compound of the formula (IV) is preferably used in an amount of 10 to 300 parts by weight, per 100 parts by weight of the compound of the formula (I').

A further photoinitiator composition (C) of the present invention comprises:

a 3-substituted coumarin compound of the formula (II),

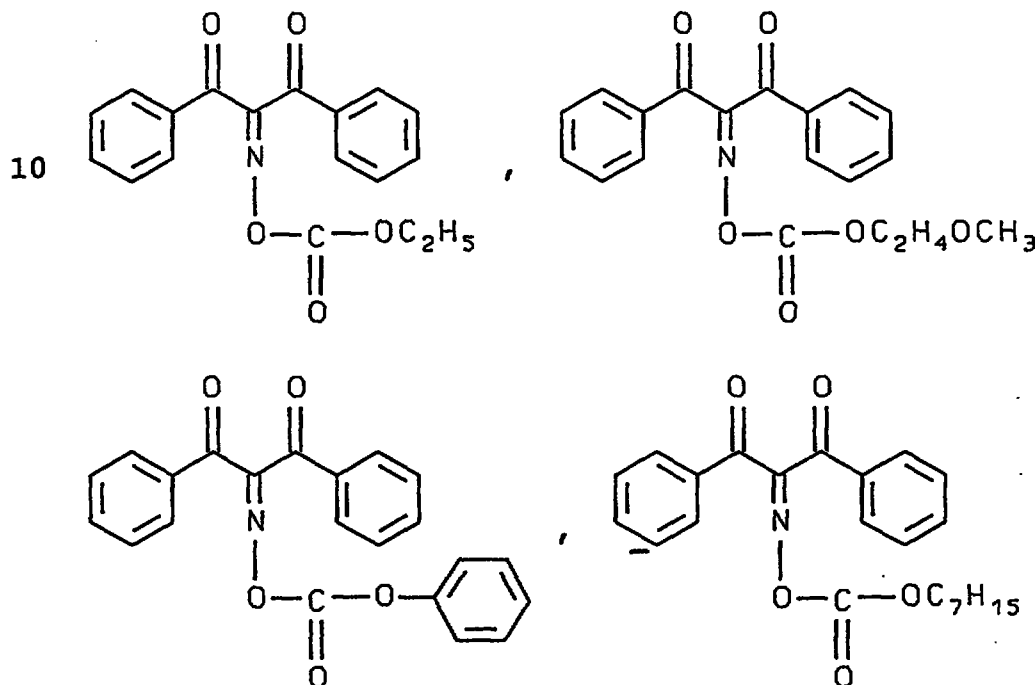
a titanocene compound of the formula (IV), and
an oxime ester compound of the formula:

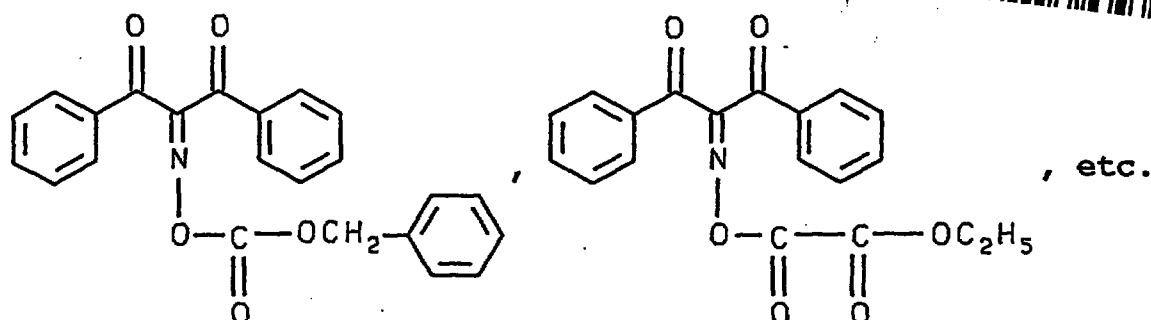


(V)

wherein R_{37} and R_{38} are independently a hydrogen atom, an alkyl group having 1 to 6 carbon atoms, an alkoxy group having 1 to 6 carbon atoms or a nitro group; and R_{39} is an
5 alkyl group having 1 to 12 carbon atoms, an alkoxy group having 1 to 12 carbon atoms, a phenyl group, a benzyl group, $-OCH_2CH_2OCH_3$ or $-CO_2CH_2CH_3$.

Examples of the oxime ester compound of the formula (V) are as follows:





These compounds can be used singly or as a mixture thereof.

The compounds of the formulae (II), (IV) and (V) may be used in various proportions, but are preferably used in amounts so as to make the titanocene compound and the oxime ester compound larger by weight than the 3-substituted coumarin compound. More concretely, the compound of the formula (II) is preferably used in an amount of 1 to 100 parts by weight, the compound of the formula (IV) is preferably used in an amount of 10 to 300 parts by weight, per 100 parts by weight of the compound of the formula (V).

The photosensitive composition of the present invention comprises

an addition polymerizable compound having a boiling point of 100°C or higher under 1 atmosphere, and a photoinitiator composition (A), (B) or (C).

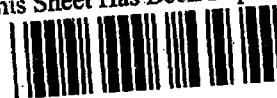
The photosensitive composition may further contain, if necessary, one or more conventional photopolymerization initiators.

Examples of the photopolymerization initiator are as follows:



Michler's ketone,
benzoin methyl ether,
benzoin ethyl ether,
benzoin isopropyl ether,
5 2-t-butylanthraquinone,
2-ethylanthraquinone,
4,4'-bis(N,N-diethylamino)benzophenone,
acetophenone,
benzophenone,
10 thioxanthone,
2,2-dimethoxy-2-phenylacetophenone,
1-hydroxycyclohexylphenyl ketone,
2-methyl-[4-(methylthio)phenyl]-2-morpholino-1-
propanone,
15 benzil,
diphenyl disulfide,
phenanthrenequinone,
2-isopropylthioxanthone,
riboflavine tetrabutyrates,
20 N-phenyldiethanolamine,
2-(O-ethoxycarbonyl)oxyimino-1,3-diphenyl-
propanedione,
1-phenyl-2-(O-ethoxycarbonyl)oxyiminopropan-1-
one,
25 3,3',4,4'-tetra(t-butylperoxycarbonyl)-
benzophenone, etc.

These photopolymerization initiators can be used singly or as a mixture thereof.



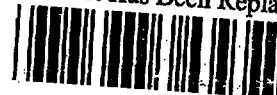
The photopolymerization initiators may be used in various proportions.

The addition polymerizable compound should have a boiling point of 100°C or higher under 1 atmosphere.

5 When the addition polymerizable compound has a boiling point of lower than 100°C under 1 atmosphere, it evaporates at the time of removing a solvent in a system, for example, by drying or at the time of irradiation with actinic radiation, resulting in giving undesirable
10 properties. Further, in order to obtain a uniform composition with a photoinitiator composition, it is preferable to use those soluble in conventionally used organic solvents.

As a solvent usable for the photosensitive
15 composition, there can be used acetone, methyl ethyl ketone, diethyl ketone, toluene, chloroform, methanol, ethanol, 1-propanol, 2-propanol, 1-butanol, 2-butanol, t-butanol, ethylene glycol monomethyl ether, ethylene glycol monoethyl ether, xylene, tetrahydrofuran, dioxane,
20 N,N-dimethylacetamide, N,N-dimethylformamide, N-methyl-2-pyrrolidone, γ -butyrolactone, dimethylsulfoxide, ethylene carbonate, propylene carbonate, sulfolane, etc. These solvents can be used singly or as a mixture thereof.

As the addition polymerizable compound having a
25 boiling point of 100°C or higher under 1 atmosphere, there can preferably be used those obtained by condensing a polyhydric alcohol with an α,β -unsaturated carboxylic acid.



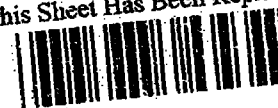
- 24 -

Examples of such compounds are as follows:

ethylene glycol di(meth)acrylate (di(meth)-acrylate means "diacrylate" or "dimethacrylate", herein-after used in this manner),

- 5 triethylene glycol di(meth)acrylate,
tetraethylene glycol di(meth)acrylate,
trimethylolpropane di(meth)acrylate,
trimethylolpropane tri(meth)acrylate,
1,2-propylene glycol di(meth)acrylate,
10 di(1,2-propylene glycol) di(meth)acrylate,
tri(1,2-propylene glycol) di(meth)acrylate,
tetra(1,2-propylene glycol) di(meth)acrylate,
dimethylaminoethyl (meth)acrylate,
diethylaminoethyl (meth)acrylate,
15 dimethylaminopropyl (meth)acrylate,
diethylaminopropyl (meth)acrylate,
1,4-butanediol di(meth)acrylate,
1,6-hexanediol di(meth)acrylate,
pentaerythritol tri(meth)acrylate,
20 pentaerythritol tetra(meth)acrylate,
styrene,
divinylbenzene,
4-vinyltoluene,
4-vinylpyridine, -
25 N-vinylpyrrolidone,
2-hydroxyethyl (meth)acrylate,
1,3-(meth)acryloyloxy-2-hydroxypropane,
methylenebisacrylamide,

THIS SHEET HAS BEEN
REPLACED



- 25 -

N,N-dimethylacrylamide,
N-methylolacrylamide, etc.

These compounds can be used singly or as a mixture thereof.

5 The photoinitiator composition (A), (B) or (C) is used in an amount of 0.01 to 30% by weight, preferably 0.05 to 10% by weight, based on the weight of the addition polymerizable compound having a boiling point of 100°C or higher under 1 atmosphere from the viewpoint of
10 photosensitivity and film strength.

The photosensitive composition of the present invention may further contain, if necessary, one or more organic polymer having a high molecular weight of preferably 10,000 to 700,000.

15 Examples of such an organic polymer are as follows:

(A) Copolyesters

Copolyesters obtained by reacting a polyhydric alcohol, for example, diethylene glycol, triethylene
20 glycol, tetraethylene glycol, trimethylolpropane, neopentyl glycol, etc. with a polyvalent carboxylic acid, for example, terephthalic acid, isophthalic acid, sebacic acid, adipic acid, etc.

(B) Vinyl polymers

25 Homopolymers or copolymers of vinyl monomers such as methacrylic acid, acrylic acid, alkyl esters of methacrylic acid or acrylic acid, for example, methyl (meth)acrylate, ethyl (meth)acrylate, butyl (meth)-



acrylate, 2-hydroxyethyl (meth)acrylate, phenyl
(meth)acrylate, benzyl (meth)acrylate, 2-dimethyl-
aminoethyl (meth)acrylate, 2-ethylhexyl (meth)acrylate,
etc.

- 5 (C) Polyformaldehydes
- (D) Polyurethanes
- (E) Polycarbonates
- (F) Polyamides
- (G) Poly(amic acid)s

10 Poly(amic acid)s can be prepared by addition
polymerization of a tetracarboxylic dianhydride and a
diamine compound.

Examples of the tetracarboxylic dianhydride are
as follows:

- 15 pyromellitic dianhydride,
- 3,3',4,4'-benzophenonetetracarboxylic
dianhydride,
- 3,3',4,4'-biphenyltetracarboxylic dianhydride,
- 1,2,5,6-naphthalenetetracarboxylic dianhydride,
- 20 2,3,6,7-naphthalenetetracarboxylic dianhydride,
- 2,3,5,6-pyridinetetracarboxylic dianhydride,
- 1,4,5,8-naphthalenetetracarboxylic dianhydride,
- 3,4,9,10-perylenetetracarboxylic dianhydride,
- 4,4'-sulfonyldipthalic dianhydride,
- 25 m-terphenyl-3,3",4,4"-tetracarboxylic
dianhydride,
- p-terphenyl-3,3",4,4"-tetracarboxylic
dianhydride,



4,4'-oxydiphthalic dianhydride,

1,1,1,3,3,3-hexafluoro-2,2-bis(2,3-dicarboxy-phenyl)propane dianhydride,

1,1,1,3,3,3-hexafluoro-2,2-bis(3,4-dicarboxy-phenyl)propane dianhydride,

2,2-bis(2,3-dicarboxyphenyl)propane dianhydride,

2,2-bis(3,4-dicarboxyphenyl)propane dianhydride,

10 1,1,1,3,3,3-hexafluoro-2,2-bis[4-(2,3-dicarboxyphenoxy)phenyl]propane dianhydride,

1,1,1,3,3,3-hexafluoro-2,2-bis[4-(3,4-dicarboxyphenoxy)phenyl]propane dianhydride, etc.

As the diamine compound, aromatic diamines,
15 heterocyclic diamines and aliphatic diamines can be used.

Examples of the aromatic diamines are as follows:

p-phenylenediamine,

m-phenylenediamine,

20 p-xylylenediamine,

m-xylylenediamine,

1,5-diaminonaphthalene,

benzidine,

3,3'-dimethylbenzidine,

25 3,3'-dimethoxybenzidine,

4,4'-(or 3,4'-, 3,3'-, or 2,4'-)diamino-diphenylmethane,

4,4'-(or 3,4'-, 3,3'-, or 2,4'-)diaminodiphenyl

ether,

4,4'-(or 3,4'-, 3,3'-, or 2,4'-)diamino-
diphenylsulfone,

4,4'-(or 3,4'-, 3,3'-, or 2,4'-)diamino-
5 diphenylsulfide,

4,4'-benzophenonediamine,

3,3'-benzophenonediamine,

4,4'-di(4-aminophenoxy)phenylsulfone,

4,4'-bis(4-aminophenoxy)biphenyl,

10 1,4-bis(4-aminophenoxy)benzene,

1,3-bis(4-aminophenoxy)benzene,

1,1,1,3,3,3-hexafluoro-2,2-bis(4-aminophenyl)-
propane,

2,2-bis[4-(4-aminophenoxy)phenyl]propane,

15 3,3'-dimethyl-4,4'-diaminodiphenylmethane,

3,3',5,5'-tetramethyl-4,4'-diaminodiphenyl-

methane,

4,4'-di(3-aminophenoxy)phenylsulfone,

3,3'-diaminodiphenylsulfone,

20 2,2'-bis(4-aminophenyl)propane, etc.

Examples of the heterocyclic diamines are as
follows:

2,6-diaminopyridine,

2,4-diaminopyrimidine,

25 2,4-diamino-s-triazine,

2,7-diaminodibenzofuran,

2,7-diaminocarbazole,

3,7-diaminophenothiazine,

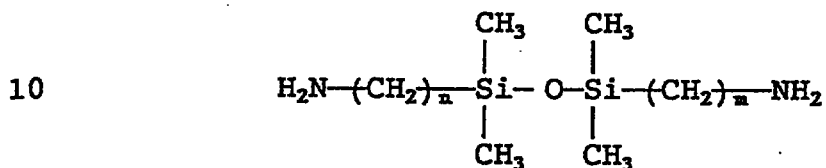


2,5-diamino-1,3,4-thiadiazole,

2,4-diamino-6-phenyl-s-triazine, etc.

Examples of the aliphatic diamines are as follows:

- 5 trimethylenediamine,
tetramethylenediamine,
hexamethylenediamine,
2,2-dimethylpropylenediamine,
diaminopolysiloxanes of the formula:



wherein n and m are the same or different integers of 1 to 10.

These tetracarboxylic dianhydrides and diamine compounds can be used singly or as a mixture thereof.

15 (H) Cellulose esters

Cellulose esters such as methyl cellulose, ethyl cellulose, etc.

By adding the organic polymer having a high molecular weight to the photosensitive composition, it is possible to improve adhesiveness to a substrate, chemical resistance, film forming properties, etc. The organic polymer having a high molecular weight can preferably be added in an amount of 20 to 80% by weight based on the total weights of the organic polymer having a high molecular weight and the addition polymerizable compound

20

25



from the viewpoint of photocurability.

In case of adding the organic polymer having a high molecular weight to the photosensitive composition, an amount of using the photoinitiator composition (A),
5 (B) or (C) is the same as the amount of using the photoinitiator composition (A), (B) or (C) described above.

Preferable examples of the photosensitive composition of the present invention are as follows:

- (i) a combination of N-(p-cyanophenyl)-glycine,
10 7-diethylamino-3-thienylcarbonyl-coumarin, bis(cyclopentadienyl)-bis[2,6-difluoro-3-(pyrrol-1-yl)phenyl]titanium, 3'-dimethylaminopropyl methacrylate and poly(amic acid) obtained by reacting 4,4'-diaminodiphenyl ether with pyromellitic dianhydride,
15 (ii) a combination of N-(p-methylsulfonylphenyl)-N-methylglycine, 7-diethylamino-3-thienylcarbonyl-coumarin, 2,6-bis(p-N,N-diethylaminobenzal)-4-methyl-4-azacyclohexanone, 3'-dimethylaminopropyl methacrylate and poly(amic acid) obtained by reacting 4,4'-diaminodiphenyl
20 ether with pyromellitic dianhydride, and
(iii) a combination of 7-diethylamino-3-thienylcarbonyl-coumarin, bis(cyclopentadienyl)-bis[2,6-difluoro-3-(pyrrol-1-yl)phenyl]titanium, 1,3-diphenyl-1,2,3-propanetrion-2-(O-ethoxycarbonyl)oxime, 3'-
25 dimethylaminopropyl methacrylate and poly(amic acid) obtained by reacting 4,4'-diaminodiphenyl ether with pyromellitic dianhydride.

The photosensitive composition may further



contain, if necessary, one or more colorants such as dyes, pigments, etc.

Examples of the colorants are fuchsin, Crystal Violet, Methyl Orange, Nile Blue 2B, Victoria pure blue,
5 Malachite Green, Night Green B, Spilon Blue, etc.

In order to enhance stability of the photo-sensitive composition during storage, it is possible to add a radical polymerization inhibitor or a radical polymerization retarder. Examples of such an inhibitor
10 or retarder are p-methoxyphenol, p-benzoquinone, hydroquinone, pyrogallol, naphthylamine, phenothiazine, aryl phosphite, nitrosoamine, etc.

The photosensitive composition of the present invention can be used as a photosensitive resin composition.
15 Further, the photosensitive composition of the present invention can contain one or more other additives such as plasticizers, adhesion promoting agents, etc.

The photosensitive material of the present invention comprises

20 (a) a poly(amic acid) such as that mentioned above,

(b) a compound having one or more carbon-carbon double bonds dimerizable or polymerizable by actinic radiation and one or more amino groups or a quaternary
25 salt thereof, said compound being selected from the addition polymerizable compound having a boiling point of 100°C or higher under 1 atmosphere, and

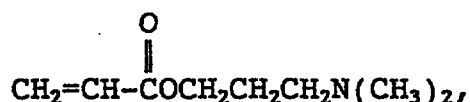
(c) a photoinitiator composition (A), (B) or



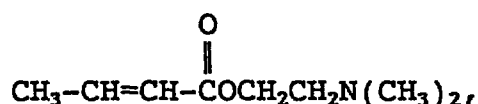
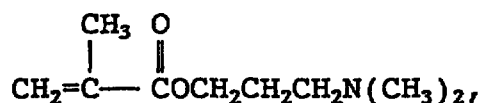
(C).

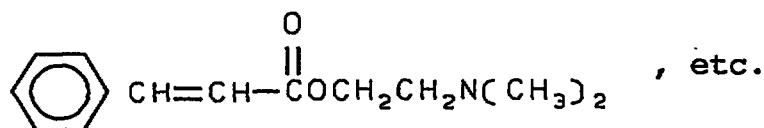
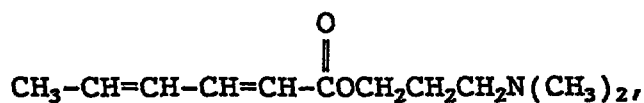
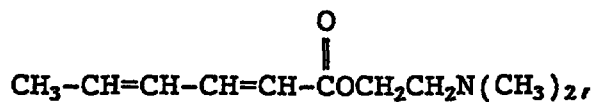
The poly(amic acid) (a) is preferably used in an equimolar amount in terms of the carboxyl group of the poly(amic acid) with regard to the compound (b). The
5 photoinitiator composition (c) is preferably used in an amount of 0.01 to 30% by weight, more preferably 0.05 to 10% by weight, based on the weight of the compound (b).

Examples of the compound (b), that is, the compound having one or more carbon-carbon double bonds
10 dimerizable or polymerizable by actinic radiation and one or more amino groups or a quaternary salt thereof, are as follows:



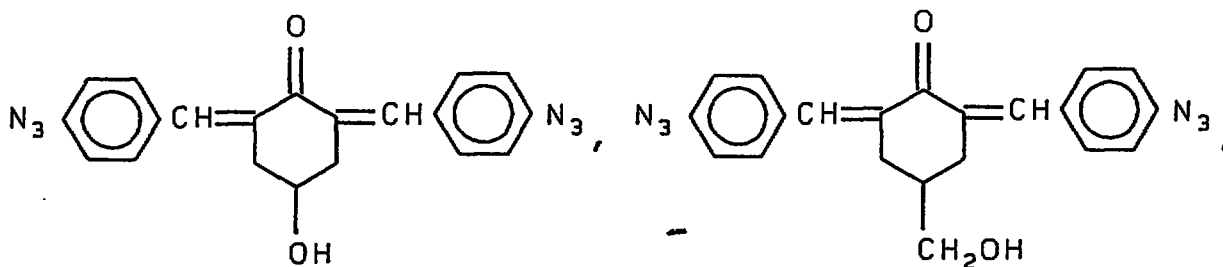
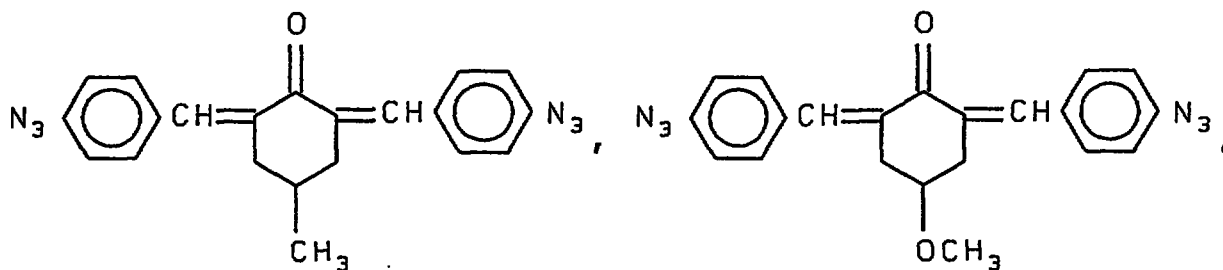
15





5 The photosensitive material may contain one or more bisazide compounds.

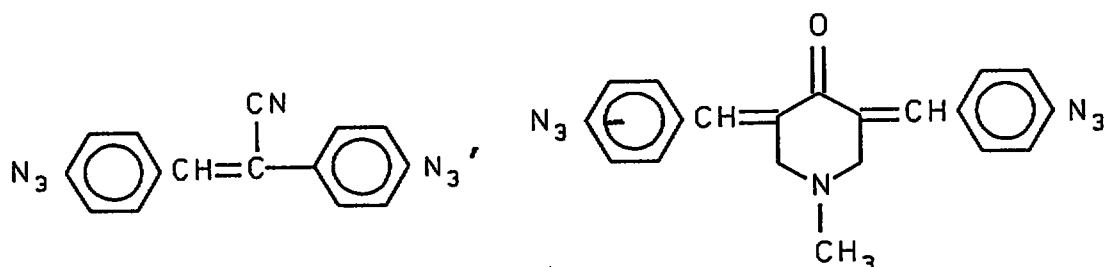
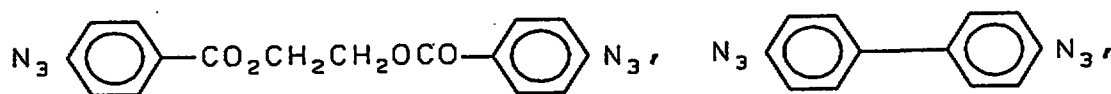
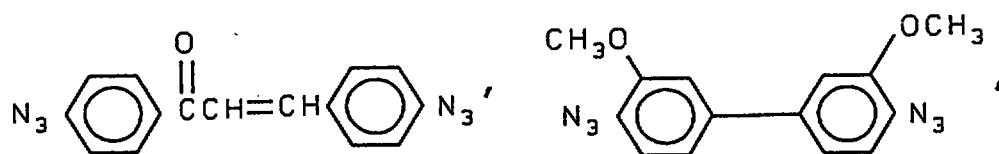
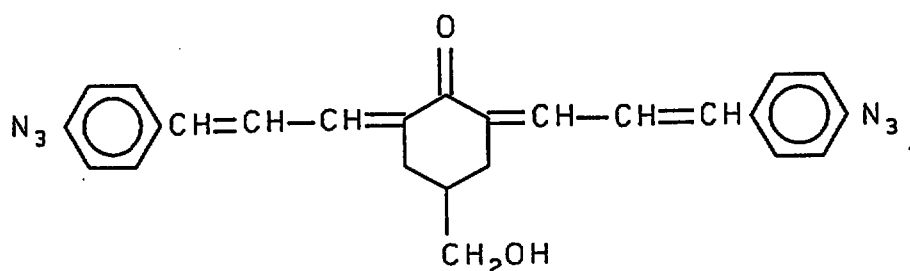
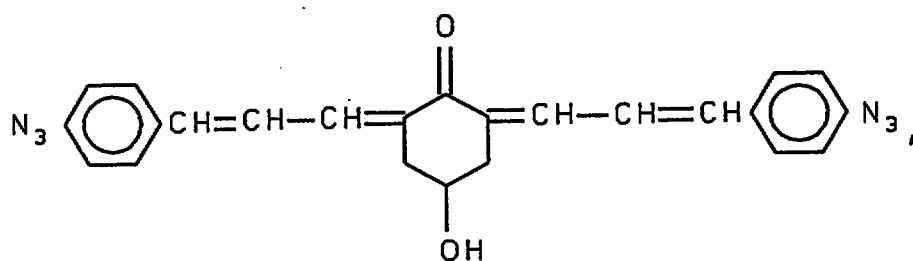
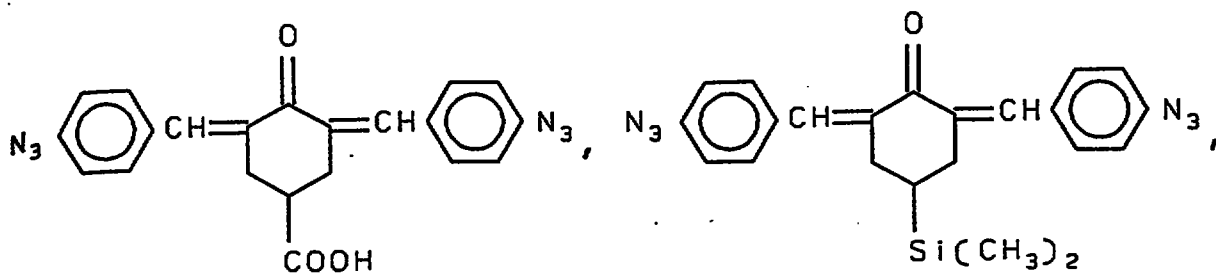
Examples of the bisazide compounds are as follows:

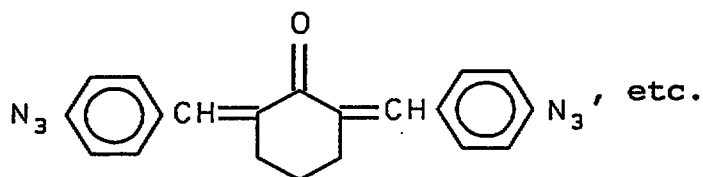
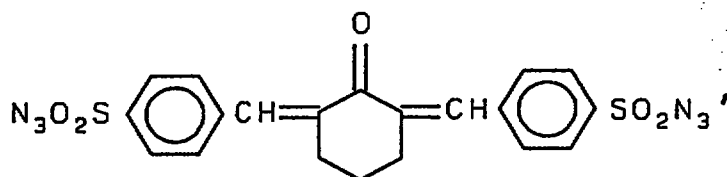
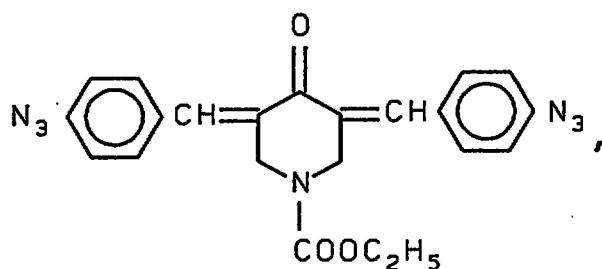
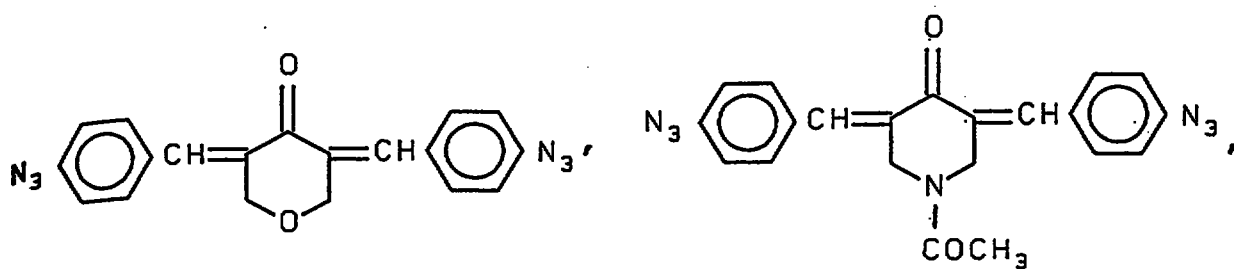


This Sheet Has Been Replaced

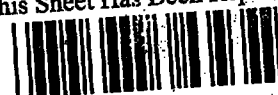


THIS SHEET HAS BEEN
REPLACED

THIS SHEET HAS BEEN
REPLACED



This Sheet Has Been Replaced

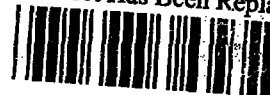


5 The bisazide compound is preferably used in an amount of 0.01 to 10% by weight based on the weight of the poly(amic acid) (a).

As a solvent for the photosensitive material, there can be used N,N-dimethylacetamide, N,N-dimethyl-
10 formamide, N-methyl-2-pyrrolidone, γ-butyrolactone, dimethylsulfoxide, sulfolane, etc., or a mixture of at least one solvent mentioned above and xylene, toluene, methyl ethyl ketone, diethyl ketone, etc.

15 The process for forming a pattern of the present invention comprises coating the photosensitive

THIS SHEET HAS BEEN
REPLACED



material on a substrate, drying the photosensitive material, exposing the photosensitive material to light, and developing the photosensitive material to give the desired pattern.

5 More concretely, the pattern formation is carried out as follows. The photosensitive material is coated on a substrate such as a silicon wafer, a metallic substrate, a glass substrate, a ceramic substrate, or the like, by an immersion method, a spray method, a screen
10 printing method, a spin coating method, etc. Almost of the solvent can be removed by drying with heating to form a coated film without sticking properties. On the coated film, a mask having a desired pattern is placed and subjected to irradiation of actinic radiation. Examples
15 of the actinic radiation are ultraviolet light, deep ultraviolet light, visible light, electron beams, X-rays, etc. After exposure to light, non-exposed portions are removed by a suitable developing solution to give a desired pattern. As the developing solution, there can
20 be used good solvents such as N,N-dimethylformamide, N,N-dimethylacetamide, N-methyl-2-pyrrolidone, etc., and a mixture of such a good solvent and a poor solvent such as lower alcohols, water, aromatic hydrocarbons, etc. After development, rinse is carried out, if necessary, with a
25 poor solvent, followed by drying at about 100°C to make the pattern stable.

The present invention is illustrated by way of Examples, in which all percents are by weight unless



otherwise specified.

Example 1

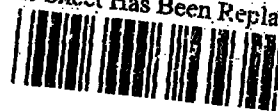
Synthesis of N-(p-methylsulfonyl)-N-methyl-glycine (Compound No. 1)

5 In a 500-ml pear-shaped flask, 4-fluoro-phenylmethanesulfone (15.01 g, 86.26 mmol), N-methyl-glycine (8.45 g, 94.89 mmol) and potassium carbonate (14.28 g, 103.48 mmol) were placed, followed by addition of 1200 ml of dimethylsulfoxide as a solvent. A
10 water cooling pipe was attached to the flask and the reaction was carried out with heating on an oil bath heated at 100°C for 9 hours with stirring using a magnetic stirrer. After cooling naturally, the reaction mixture was dissolved in 1 liter of water, and subjected
15 to acidolysis with 1/10N HCl, followed by filtration of a precipitate. After washing with water well, the precipitate was washed with hexane/benzene (4/1 in volume ratio). The yield of the product after dried was 12.13 g (49.92 mmol, 57.9%). The melting point was 161.2°C.

20 Example 2

Synthesis of N-(p-cyanophenyl)-glycine
(Compound No. 2)

 In a 500-ml three-necked flask, 4-cyanoaniline (100 g, 847.4 mmol) was placed, followed by addition of
25 300 ml of water and attachment of a water cooling pipe, a mechanical stirrer and a dropping funnel. The flask was



- heated on an oil bath heated at 100°C. To the flask, an aqueous solution (water 150 ml) of monochloroacetic acid (104 g, 1116 mmols) was added dropwise for about 30 minutes, followed by reflux with heating for 2.5 hours.
- 5 After cooling naturally, about 100 ml of ethyl acetate was added to the flask to dissolve an insoluble matter. An organic layer was separated by a separatory funnel. The residual water layer and an aqueous layer obtained by extracting the organic layer with 100 ml of 5% (by
- 10 weight) NaOH solution were combined, followed by acidolysis with 1/10N HCl. A precipitate produced was filtered and washed with water several times. After drying in an oven heated at 60°C for 3 hours, the dried precipitate was dried in a vacuum desiccator overnight.
- 15 The resulting product was a beige powder which showed no melting point but decomposed at 233.1°C. The yield was 38.8 g (26%).

Example 3

Synthesis of N-(p-cyanophenyl)-N-methylglycine

20 (Compound No. 3)

- In a 500-ml pear-shaped flask, 4-fluorobenzonitrile (10.44 g, 86.26 mmols), N-methylglycine (8.45 g, 94.89 mmols) and potassium carbonate (14.28 g, 103.48 mmols) were placed, followed by addition of 200
- 25 ml of dimethylsulfoxide as a solvent. A water cooling pipe was attached to the flask, and the reaction was carried out with heating on an oil bath heated at 100°C



for 9 hours with stirring using a magnetic stirrer.

After cooling naturally, the reaction mixture was dissolved in 1 liter of water and subjected to acidolysis with 1/10N HCl, followed by filtration of a precipitate.

- 5 After washing with water well, the precipitate was washed with hexane/benzene (4/1 in volume ratio). The yield of the product after dried was 14.21 g (74.79 mmoles, 86.7%). The melting point was 64.5°C.

The structure of the Compound Nos. 1 to 3 was
10 confirmed by H^1 -NMR spectra shown in Table 1.

Table 1

Compound No.	Chemical shift	Number of proton	Kind of proton	Coupling constant (Hz)
1	3.00(s)	3H	CH_3SO_3-Ar-	-
	3.15(s)	3H	$N-CH_3$	-
	4.11(s)	2H	$N-CH_2-CO_2H$	-
	6.73(d)	2H	Ar-H	9.03
	7.72(d)	2H	Ar-H	8.96
2	4.04(d)	2H	$N-CH_2-CO_2H$	5.20
	6.08(s)	1H	NH	-
	6.78(d)	2H	Ar-H	8.80
	7.47(d)	2H	Ar-H	8.80
3	3.12(s)	3H	$N-CH_3$	-
	4.15(s)	2H	$N-CH_2-CO_2H$	-
	6.65(d)	2H	Ar-H	9.09
	7.49(d)	2H	Ar-H	9.10



Examples 4 to 8, Comparative Examples 1 and 2

A photosensitive material was prepared by mixing 10 g of N-methyl-2-pyrrolidone solution of poly(amic acid) (solid content 20%) obtained by reacting 5 4,4'-diaminodiphenyl ether with pyromellitic dianhydride in equimolar amounts, 1.8 g of 2-dimethylaminoethyl methacrylate, and a photoinitiator composition (A) as shown in Table 2 with stirring.

After filtering with a filter, the 10 photosensitive material was spin coated on a silicon wafer. After heating on a hot plate at 100°C for 200 seconds, the solvent was removed to give a photosensitive coated film. The film thickness after dried was 10 μm .

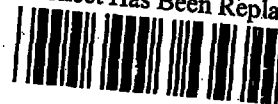
The photosensitive coated film was exposed to 15 light via a photomask using a ultrahigh pressure mercury lamp. The light exposure amount was 500 mJ/cm^2 . The resulting film was subjected to immersion development using a mixed solution of N-methyl-2-pyrrolidone and methyl alcohol (4/1 in volume ratio), followed by rinsing 20 with isopropanol. After development, the shape of pattern was measured and observed. A normalized film thickness after development (NFTAD) (a value obtained by dividing the film thickness by the initial time film thickness) and a minimum open-through-hole diameter (open 25 diameter) were shown in Table 2.

In Example 4, wherein N-(p-methylsulfonyl-phenyl)-N-methylglycine was used for the wafer, the finally cured film was obtained by heating at 100°C for

15 minutes, at 200°C for 20 minutes and at 350°C for 60 minutes in a nitrogen atmosphere. The film thickness of finally cured film was 5 μ m with good polyimide pattern.

As shown in Table 2, according to the data of
5 NFTAD and open diameter, the evaluation that the
photosensitive materials of the present invention have an
excellent resolution can be admitted, therefore the
photosensitive materials of the present invention are
excellent in photosensitive properties compared with
10 Comparative Examples.

This Sheet Has Been Replaced



THIS SHEET HAS BEEN
REPLACED

Table 2

Example No.		Example					Comparative Example	
		4	5	6	7	8	1	2
Photo-initiator composition (A)	DETC	10mg	10mg	10mg	0	0	10mg	0
	ACH	0	0	0	10mg	10mg	0	10mg
	Compound No.1	100mg	0	0	100mg	0	0	0
	Compound No.2	0	100mg	0	0	100mg	0	0
	Compound No.3	0	0	100mg	0	0	0	0
Evaluation	NFTAD (X)	98	97	98	96	99	65	0
	Open diameter (μm)	8	8	8	8	8	10	No pattern was obtained

Note) DETC = 7-N,N-diethylamino-3-thienylcarbonyl-coumarin

ACH = 2,6-bis(p-N,N-diethylaminobenzal)-4-methyl-azacyclohexanone

This Sheet Has Been Replaced



THIS SHEET HAS BEEN
REPLACED

Examples 9 to 14, Comparative Examples 3 to 5

N-(p-cyanophenyl)-glycine was synthesized in the same manner as described in Example 2.

N-(p-cyanophenyl)-N-methylglycine was
5 synthesized in the same manner as described in Example 3.

A photosensitive material was prepared by mixing 10 g of N-methyl-2-pyrrolidone solution of poly(amic acid) (solid content 20%) obtained by reacting 4,4'-diaminodiphenyl ether with pyromellitic dianhydride
10 in equimolar amounts, 1.8 g of 2-dimethylaminoethyl methacrylate, and a photoinitiator composition (B) as shown in Table 3 with stirring.

A pattern was formed and the normalized film thickness after development (NFTAD) and open diameter
15 were measured in the same manner as described in Examples 4 to 8, and listed in Table 3. In Table 3, the shape of pattern was also listed.

As to the wafer of Example 12, the finally cured film was obtained by heating at 100°C for 15
20 minutes, at 200°C for 20 minutes and at 350°C for 60 minutes in a nitrogen atmosphere. The film thickness of finally cured film was 10 μ m with good polyimide pattern.

As shown in Table 3, according to the data of NFTAD and the open diameter, the evaluation that the
25 photosensitive materials of the present invention have an excellent resolution can be admitted, therefore the photosensitive materials of the present invention are

This Sheet Has Been Replaced



THIS SHEET HAS BEEN
REPLACED

excellent in photosensitive properties compared with
Comparative Examples.

This Sheet Has Been Replaced



THIS SHEET HAS BEEN
REPLACED

Table 3

Example No.		Example						Comparative Example		
		9	10	11	12	13	14	3	4	5
Photo-initiator composition (B)	BC	10mg	0	0	10mg	10mg	0	10mg	0	0
	MOBC	0	10mg	0	0	0	10mg	0	0	0
	DETC	0	0	10mg	0	0	0	0	0	0
	Titanocene 1	100mg	100mg	100mg	100mg	100mg	100mg	0	100mg	100mg
	Compound No.2	0	0	0	100mg	0	100mg	100mg	0	100mg
	Compound No.3	0	0	0	0	100mg	0	0	0	0
Evaluation	NFTAD (X)	78	77	78	96	99	95	60	25	25
	Open diameter (μm)	8	8	8	8	8	10	20	100	100
	Shape of pattern	Good	Good	Good	Good	Good	Good	Undercut	Swollen	Swollen

Note) BC = 3,3'-carbonylbis-(7-diethylamino-coumarin)
 MOBC = 3,3'-carbonylbis-(7-methoxy-coumarin)
 DETC = 7-N,N-diethylamino-3-thienylcarbonyl-coumarin
 Titanocene 1 = bis(cyclopentadienyl)-bis[2,6-difluoro-3-(pyrrol-1-yl)phenyl]titanium

This Sheet Has Been Replaced

THIS SHEET HAS BEEN
REPLACED

Examples 15 to 20, Comparative Examples 6 to 8

To the same photosensitive materials used in Examples 9 to 14 and Comparative Examples 3 to 5, 20 mg of 4,4'-bisazido-3,3'-dimethoxybiphenyl (AZ) was added and 5 subjected to the same tests as in Examples 15 to 20.

The results are shown in Table 4.

As shown in Table 4, according to the data of NFTAD and open diameter, the evaluation that the photosensitive materials of the present invention have an 10 excellent resolution can be admitted, and by the addition of bisazide compound, the normalized film thickness after development is improved.

This Sheet Has Been Replaced



THIS SHEET HAS BEEN
REPLACED

Table 4

Example No.		Example						Comparative Example		
		15	16	17	18	19	20	6	7	8
Photo-initiator composition (B)	BC	10mg	0	0	10mg	10mg	0	10mg	0	0
	MOBC	0	10mg	0	0	0	10mg	0	0	0
	DETC	0	0	10mg	0	0	0	0	0	0
	Titanocene 1	100mg	100mg	100mg	100mg	100mg	100mg	0	100mg	100mg
	Compound No.2	0	0	0	100mg	0	100mg	100mg	0	100mg
	Compound No.3	0	0	0	0	100mg	0	0	0	0
Additive	AZ	20mg	20mg	20mg	20mg	20mg	20mg	20mg	20mg	20mg
Evaluation	NFTAD (Z)	85	85	85	100	100	100	65	30	30
	Open diameter (μm)	8	8	8	8	8	10	20	100	100
	Shape of pattern	Good	Good	Good	Good	Good	Good	Undercut	Swollen	Swollen

THIS SHEET HAS BEEN
REPLACED

This Sheet Has Been Replaced



Examples 21 to 26, Comparative Examples 9 to 14

A photosensitive material was prepared by mixing 10 g of N-methyl-2-pyrrolidone solution of poly(amic acid) (solid content 20%) obtained by reacting 5 4,4'-diaminodiphenyl ether with pyromellitic dianhydride in equimolar amounts, 1.8 g of 2-dimethylaminoethyl methacrylate, and a photoinitiator composition (C) as shown in Table 5 with stirring.

A pattern was formed and the normalized film 10 thickness after development (NFTAD) and open diameter were measured in the same manner as described in Examples 4 to 8, and listed in Table 5. In Table 5, the shape of pattern was also listed.

As to the wafer of Example 24, the finally 15 cured film was obtained by heating at 100°C for 15 minutes, at 200°C for 20 minutes, and at 350°C for 60 minutes in a nitrogen atmosphere. The film thickness of finally cured film was 10 μ m with good polyimide pattern.

As shown in Table 5, according to the data of 20 NFTAD and open diameter, the evaluation that the photosensitive materials of the present invention have an excellent resolution can be admitted, therefore the photosensitive materials of the present invention are excellent in photosensitive properties compared with 25 those of Comparative Examples.

This Sheet Has Been Replaced



THIS SHEET HAS BEEN
REPLACED

Table 5

Example No.		Example						Comparative Example					
		21	22	23	24	25	26	9	10	11	12	13	14
Photo-initia- tor composi- tion (C)	BC	10mg	0	0	10mg	0	0	10mg	10mg	0	0	0	0
	MOBC	0	10mg	0	0	10mg	0	0	0	0	0	0	0
	DETC	0	0	10mg	0	0	10mg	0	0	0	0	0	0
	Titanocene 1	100mg	100mg	100mg	100mg	100mg	100mg	0	0	100mg	100mg	100mg	100mg
	Oxime ester 1	100mg	100mg	100mg	100mg	100mg	100mg	100mg	100mg	0	0	100mg	100mg
Additive	AZ	0	0	0	20mg	20mg	20mg	0	20mg	0	20mg	0	20mg
Evalua- tion	NFTAD (%)	75	75	75	85	85	85	60	65	25	30	25	30
	Open diameter (μ m)	10	10	10	10	10	10	20	20	100	100	100	100
	Shape of pattern	Good	Good	Good	Good	Good	Good	Undercut	Undercut	Swol- len	Swol- len	Swol- len	Swol- len

Note) Oxime ester 1 = 1,3-diphenyl-1,2,3-propanetrion-2-(O-ethoxycarbonyl)oxime

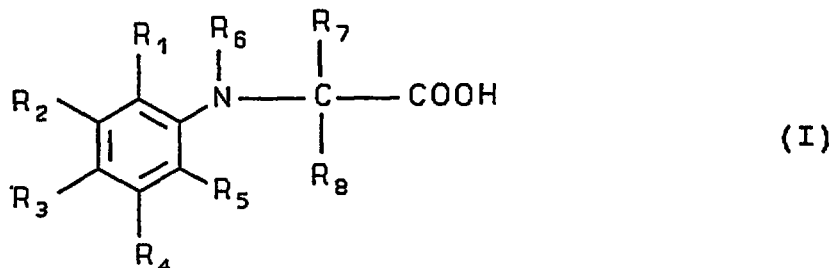
THIS SHEET HAS BEEN
REPLACED

This Sheet Has Been Replaced



CLAIMS

1. An N-aryl- α -amino acid of the formula:



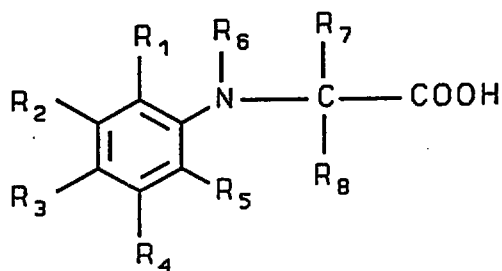
wherein R_1 , R_2 , R_3 , R_4 and R_5 are independently a hydrogen atom, a halogen atom, an alkyl group having 1 to 4 carbon atoms, a cyano group, an alkoxy carbonyl group having 2 to 10 carbon atoms, a carboxyamido group or an alkylsulfonyl group having 1 to 4 carbon atoms and said alkyl moiety able to be substituted with a cyano group, and at least one of R_1 through R_5 is a cyano group or an alkylsulfonyl group having 1 to 4 carbon atoms; R_6 is a hydrogen atom, an alkyl group having 1 to 12 carbon atoms, a cycloalkyl group, a hydroxyalkyl group having 1 to 12 carbon atoms, an alkoxyalkyl group having 2 to 12 carbon atoms, an aminoalkyl group having 1 to 12 carbon atoms, or an aryl group; and R_7 and R_8 are independently a hydrogen atom or an alkyl group having 1 to 8 carbon atoms.

2. A photoinitiator composition (A) comprising an N-aryl- α -amino acid of the formula:

This Sheet Has Been Replaced



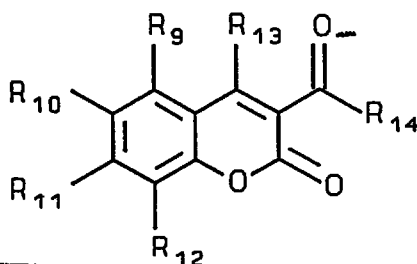
THIS SHEET HAS BEEN
REPLACED



(I')

wherein R_1 , R_2 , R_3 , R_4 and R_5 are independently a hydrogen atom, a halogen atom, an alkyl group having 1 to 4 carbon atoms, a cyano group, an alkoxycarbonyl group having 2 to 10 carbon atoms, a carboxyamido group, or an alkylsulfonyl group having 5 1 to 4 carbon atoms and said alkyl moiety being able to be substituted with a cyano group; R_6 is a hydrogen atom, an alkyl group having 1 to 12 carbon atoms, a cycloalkyl group, a hydroxyalkyl group having 1 to 12 carbon atoms, an alkoxyalkyl group having 2 to 12 carbon atoms, an aminoalkyl 10 group having 1 to 12 carbon atoms, or an aryl group; and R_7 and R_8 are independently a hydrogen atom or an alkyl group having 1 to 8 carbon atoms, and

at least one member selected from the group consisting of a 3-substituted coumarin compound of the 15 formula:



(II)

This Sheet Has Been Replaced



THIS SHEET HAS BEEN
REPLACED

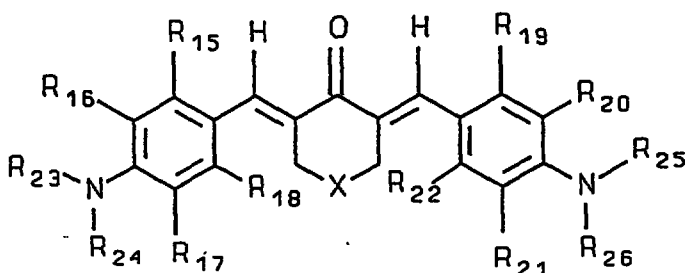


This Sheet Has Been Replaced



- 52 -

wherein R_9 , R_{10} , R_{11} , R_{12} and R_{13} are independently a hydrogen atom, an amino group substituted with an alkyl group having 1 to 5 carbon atoms, an amino group substituted with two alkyl groups having 1 to 5 carbon atoms, an alkoxy group having 1 to 5 carbon atoms, an acyloxy group, an aryl group, a halogen atom, or a thioalkyl group having 1 to 5 carbon atoms; and R_{14} is a non-substituted phenyl group, a biphenyl group, a naphthyl group, a thienyl group, a benzofuryl group, a furyl group, a pyridyl group, a coumarinyl group, an amino group, 10 an amino group substituted with one or more alkyl groups having 1 to 5 carbon atoms, a cyano group, an alkoxy group having 1 to 5 carbon atoms, an alkyl group having 1 to 5 carbon atoms, a halogen atom, a haloalkyl group, a formyl group, an alkoxycarbonyl group having 1 to 5 carbon atoms, an 15 acyloxy group having 1 to 5 carbon atoms, a phenyl group substituted with an acyloxy group having 1 to 5 carbon atoms, a cyano group, an alkoxy group or an acyl group having 1 to 5 carbon atoms, said biphenyl group, said naphthyl group, said thienyl group, said benzofuryl group, said furyl group, said 20 pyridyl group or said coumarinyl group being able to be substituted with an acyloxy group having 1 to 5 carbon atoms or an acyl group having 1 to 5 carbon atoms, and an azabenzalicyclohexanone compound of the formula:



(III)

THIS SHEET HAS BEEN
REPLACED



This Sheet Has Been Replaced



- 53 -

wherein R_{15} , R_{16} , R_{17} , R_{18} , R_{19} , R_{20} , R_{21} and R_{22} are independently a hydrogen atom, a chlorine atom, a bromine atom, an alkyl group having 1 to 12 carbon atoms, an aryl group or an alkoxy group having 1 to 12 carbon atoms; and R_{23} , R_{24} , R_{25} and R_{26} are
5 independently an alkyl group having 1 to 6 carbon atoms; X is an imino group which may be substituted with an alkyl group having 1 to 12 carbon atoms, an aralkyl group having 7 to 20 carbon atoms, an aryl group, an acyl group having 2 to 12 carbon atoms, an arylcarbonyl group having 7 to 20 carbon
10 atoms, an alkoxycarbonyl group having 2 to 12 carbon atoms, or an aryloxy carbonyl group having 7 to 20 carbon atoms.

3. A photosensitive composition comprising an addition polymerizable compound having a boiling point of 100°C or higher under 1 atmosphere, and
15 a photoinitiator composition (A) of claim 2.

4. A photosensitive composition according to claim 3, which further comprises one or more organic polymers having a high molecular weight.

5. A photosensitive material comprising
20 (a) a poly(amic acid),
(b) a compound having one or more carbon-carbon double bonds dimerizable or polymerizable by actinic radiation and one or more amino groups or a quaternary salt thereof, and
25 (c) a photoinitiator composition (A) of claim 2.

6. A photosensitive material according to claim 5, which further comprises one or more bisazide compounds.

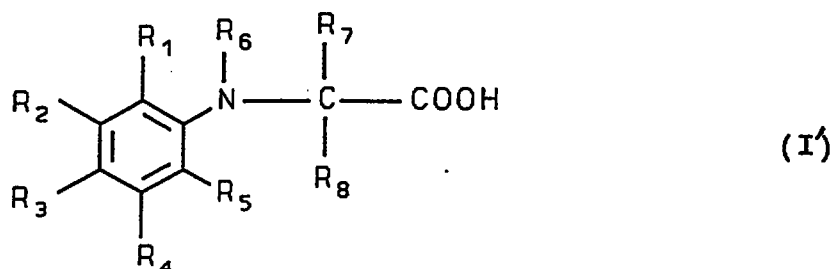
THIS SHEET HAS BEEN
REPLACED



- 54 -

7. Use of a photosensitive material of claim 5 for forming a pattern.

8. A photoinitiator composition (B) comprising an N-aryl- α -amino acid of the formula:



5 wherein R_1 , R_2 , R_3 , R_4 and R_5 are independently a hydrogen atom, a halogen atom, an alkyl group having 1 to 4 carbon atoms, a cyano group, an alkoxycarbonyl group having 2 to 10 carbon atoms, a carboxyamido group, or an alkylsulfonyl group having 1 to 4 carbon atoms and said alkyl moiety being able to be
10 substituted with a cyano group; R_6 is a hydrogen atom, an alkyl group having 1 to 12 carbon atoms, a cycloalkyl group, a hydroxyalkyl group having 1 to 12 carbon atoms, an alkoxyalkyl group having 2 to 12 carbon atoms, an aminoalkyl group having 1 to 12 carbon atoms, or an aryl group; and R_7
15 and R_8 are independently a hydrogen atom or an alkyl group having 1 to 8 carbon atoms,

a 3-substituted coumarin compound of the formula:

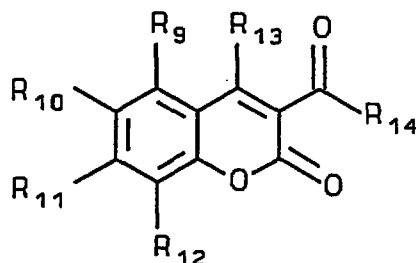
This Sheet Has Been Replaced



THIS SHEET HAS BEEN
REPLACED



- 55 -



(II)

wherein R_9 , R_{10} , R_{11} , R_{12} and R_{13} are independently a hydrogen atom, an amino group substituted with an alkyl group having 1 to 5 carbon atoms, an amino group substituted with two alkyl groups having 1 to 5 carbon atoms, an alkoxy group having 1 to 5 carbon atoms, an acyloxy group, an aryl group, a halogen atom, or a thioalkyl group having 1 to 5 carbon atoms; and R_{14} is a non-substituted phenyl group, a biphenyl group, a naphthyl group, a thienyl group, a benzofuryl group, a furyl group, a pyridyl group, a coumaryl group, an amino group, an amino group substituted with one or more alkyl groups having 1 to 5 carbon atoms, a cyano group, an alkoxy group having 1 to 5 carbon atoms, an alkyl group having 1 to 5 carbon atoms, a halogen atom, a haloalkyl group, a formyl group, an alkoxycarbonyl group having 1 to 5 carbon atoms, an acyloxy group having 1 to 5 carbon atoms, a phenyl group substituted with an acyloxy group having 1 to 5 carbon atoms, a cyano group, an alkoxy group or an acyl group having 1 to 5 carbon atoms, said biphenyl group, said naphthyl group, said thienyl group, said benzofuryl group, said furyl group, said pyridyl group or said coumarinyl group being able to be substituted with an acyloxy group having 1 to 5 carbon atoms or an acyl

This Sheet Has Been Replaced

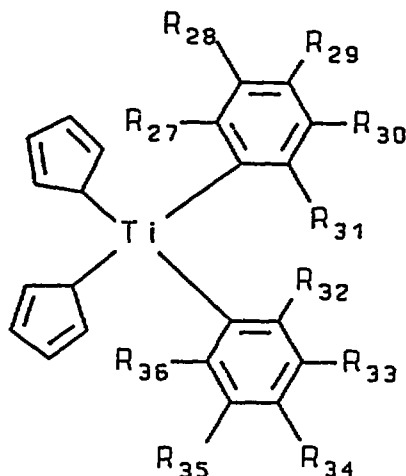


THIS SHEET HAS BEEN
REPLACED



group having 1 to 5 carbon atoms, and

a titanocene compound of the formula:



(IV)

wherein R_{27} through R_{36} are independently a hydrogen atom, a halogen atom, an alkoxy group having 1 to 20 carbon atoms or a heterocyclic ring, said heterocyclic ring being bound to a benzene ring via an alkylene group or substituted with one or more alkyl groups, amino groups and alkoxy groups.

9. A photosensitive composition comprising an addition polymerizable compound having a boiling point of 100°C or higher under 1 atmosphere, and a photoinitiator composition (B) of claim 8.

10. A photosensitive composition according to claim 9, which further comprises one or more organic polymers having a high molecular weight.

11. A photosensitive material comprising
(a) a poly(amic acid),
(b) a compound having one or more carbon-carbon double bonds dimerizable or polymerizable by actinic





- 57 -

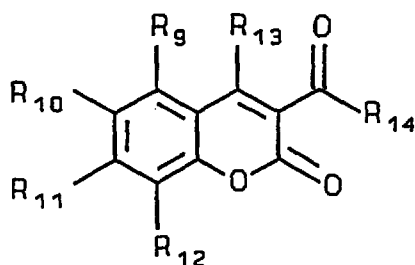
radiation and one or more amino groups or a quaternary salt thereof, and

(c) a photoinitiator composition (B) of claim 8.

12. A photosensitive material according to claim 5 11, which further comprises one or more bisazide compounds.

13. Use of a photosensitive material of claim 11 for forming a pattern.

14. A photoinitiator composition (C) comprising a 3-substituted coumarin compound of the formula:



10 wherein R_9 , R_{10} , R_{11} , R_{12} and R_{13} are independently a hydrogen atom, an amino group substituted with an alkyl group having 1 to 5 carbon atoms, an amino group substituted with two alkyl groups having 1 to 5 carbon atoms, an alkoxy group having 1 to 5 carbon atoms, an acyloxy group, an aryl group, a halogen
15 atom, or a thioalkyl group having 1 to 5 carbon atoms; and R_{14} is a non-substituted phenyl group, a biphenyl group, a naphthyl group, a thienyl group, a benzofuryl group, a furyl group, a pyridyl group, a coumaryl group, an amino group, an amino group substituted with one or more alkyl groups having
20 1 to 5 carbon atoms, a cyano group, an alkoxy group having 1

This Sheet Has Been Replaced



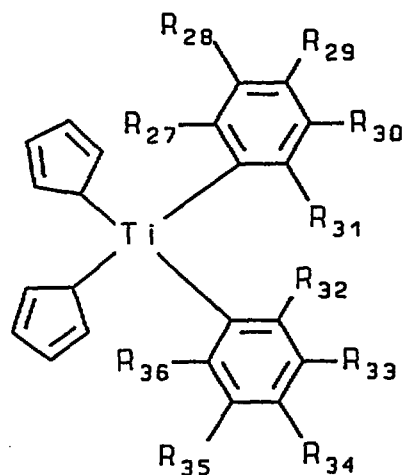
THIS SHEET HAS BEEN
REPLACED



- 58 -

to 5 carbon atoms, an alkyl group having 1 to 5 carbon atoms, a halogen atom, a haloalkyl group, a formyl group, an alkoxy carbonyl group having 1 to 5 carbon atoms, an acyloxy group having 1 to 5 carbon atoms, a phenyl group substituted with an acyloxy group having 1 to 5 carbon atoms, a cyano group, an alkoxy group, or an acyl group having 1 to 5 carbon atoms, said biphenyl group, said naphthyl group, said thienyl group, said benzofuryl group, said furyl group, said pyridyl group or said coumarinyl group being able to be substituted with an acyloxy group having 1 to 5 carbon atoms or an acyl group having 1 to 5 carbon atoms,

a titanocene compound of the formula:



(IV)

wherein R_{27} through R_{36} are independently a hydrogen atom, a halogen atom, an alkoxy group having 1 to 20 carbon atoms or a heterocyclic ring which may be bound to a benzene ring via an alkylene group or substituted with one or more alkyl groups, amino groups and alkoxy groups, and

an oxime ester compound of the formula:

This Sheet Has Been Replaced

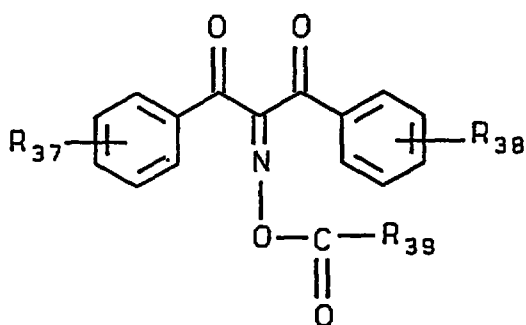


THIS SHEET HAS BEEN
REPLACED



- 59 -

This Sheet Has Been Replaced



wherein R_{37} and R_{38} are independently a hydrogen atom, an alkyl group having 1 to 6 carbon atoms, an alkoxy group having 1 to 6 carbon atoms or a nitro group; and R_{39} is an alkyl group having 1 to 12 carbon atoms, an alkoxy group having 1 to 12 carbon atoms, a phenyl group, a benzyl group, $-\text{OCH}_2\text{CH}_2\text{OCH}_3$, or $-\text{CO}_2\text{CH}_2\text{CH}_3$.

15. A photosensitive composition comprising
an addition polymerizable compound having a
boiling point of 100°C or higher under 1 atmosphere, and
10 a photoinitiator composition (C) of claim 14.

16. A photosensitive composition according to
claim 15, which further comprises one or more organic
polymers having a high molecular weight.

17. A photosensitive material comprising
15 (a) a poly(amic acid),
(b) a compound having one or more carbon-carbon
double bonds dimerizable or polymerizable by actinic
radiation and one or more amino groups or quaternary salt
thereof, and

20 (c) a photoinitiator composition (C) of claim
14.

18. A photosensitive material according to claim

THIS SHEET HAS BEEN
REPLACED



- 60 -

17, which further comprises one or more bisazide compounds.

19. Use of a photosensitive material of claim 17 for forming a pattern.

20. A process for forming a pattern, which
5 comprises coating a photosensitive material of claim 5, 11 or 17 on a substrate, drying the photosensitive material, exposing the photosensitive material to light, and developing the photosensitive material.

21. Use of an N-aryl- α -amino acid of the formula
10 (I') as defined in claim 2 as a photoinitiator.

This Sheet Has Been Replaced



THIS SHEET HAS BEEN
REPLACED